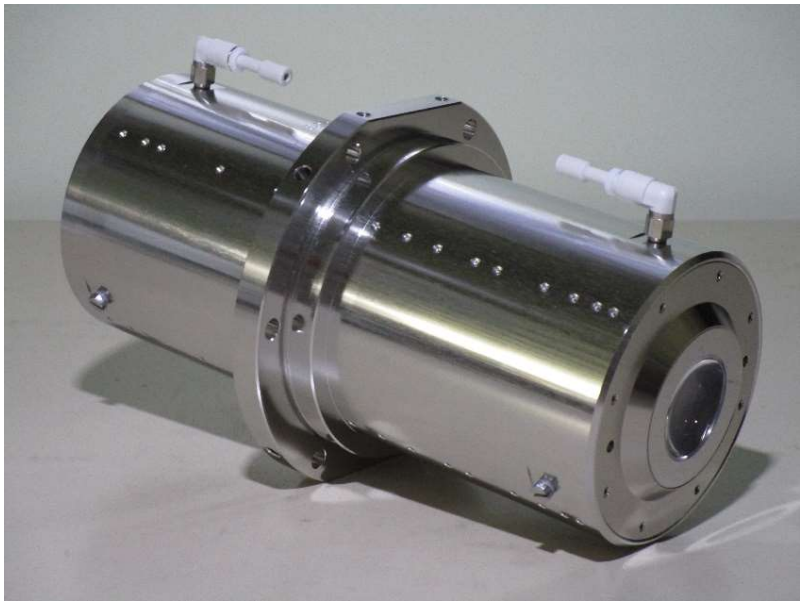
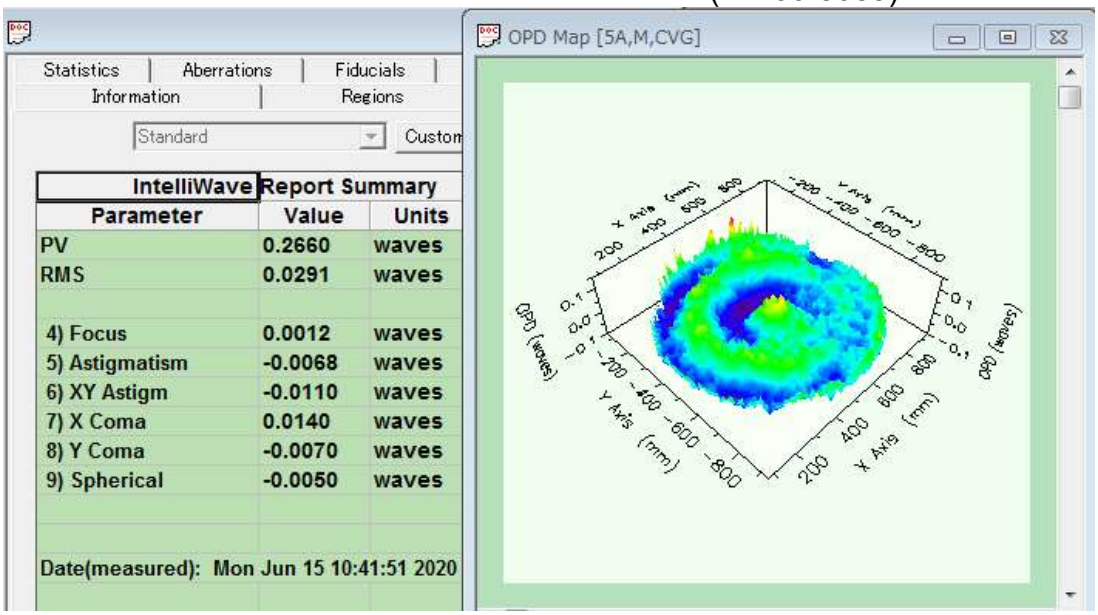
Objective lenses for mask / wafer inspection

Features
- ◎ From its refractive optical system, it has no shielding and long working distance.
- ◎ It is achromatic within the spectrum of the laser, resulting in good imaging properties.
- ◎ The design performance is numerically guaranteed by measuring wavefront aberration with an interferometer.
- ◎ Suitable for semiconductor mask / wafer observation applications.



The MI series of objective lenses for mask / wafer inspection have co-functioning with a wide field of view, long working distance, and aberration-free, that results in high suitability for semiconductor photomask / wafer inspection.
Custom arrangement is available for the various relay lenses.

- Sample for an evaluation of transmitted wavefront aberration (MI266-5085)



Optical components, optical systems, lasers

KYOCERA SOC Corporation

Contact us:
TEL:+81-45-931-6592
URL: https://www.ksoc.co.jp/en/shiryo/
Responsible for sales: Kobayashi and Kimura

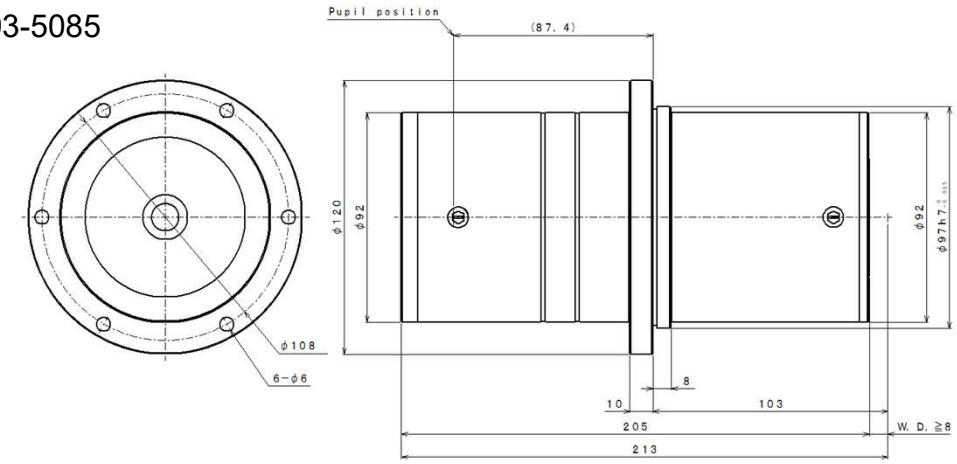
Objective lenses for mask / wafer inspection

● Lineup

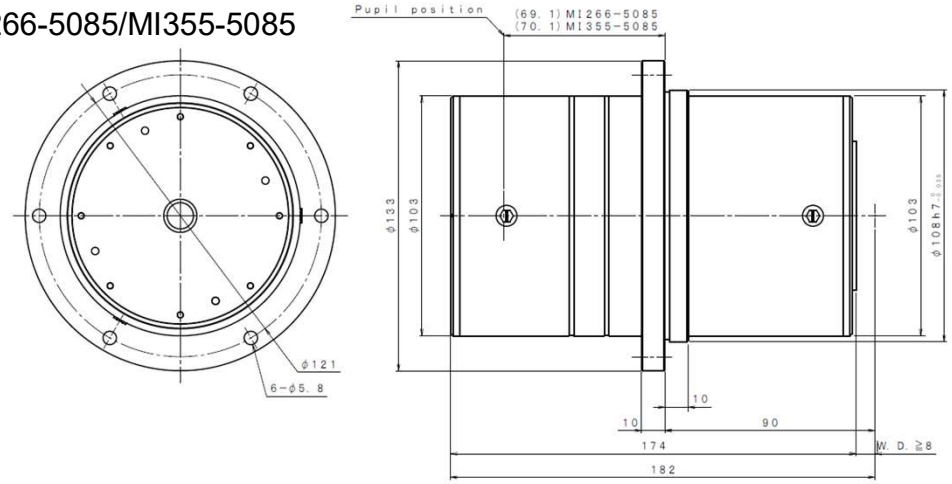
Model name	MI193-5085	MI266-5085	MI355-5085
Wavelength	193nm	266nm	355nm
Bandwidth (full width at half maximum)	8pm	5pm	20pm
Type	Refractive type		
Numerical aperture (NA)	0.85		
Focal length	5mm		
Transmittance	70% or more	80% or more	
Field of view	φ0.3mm	φ0.45mm	
Wavefront aberration (monochromatic)	≦ 0.03 waves rms		
Working distance	≧ 8mm		
Weight	Approx. 6.5kg	Approx. 7.1kg	Approx. 7kg
Operating temperature	23±0.5℃		

● External Dimensions

MI193-5085



MI266-5085/MI355-5085



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